Computer Sinulation of Self-Organization in Block Copolymers

BackgroundMethodResults

The Physics of Block Copolymers, Ian W. Hamley, Oxford University Press, 1998

Block Copolymers: Past Successes and Future Challenges, Timothy P. Lodge, *Macromol. Chem. Phys.* 2003, **204**, pp 265-273

Monte Carlo

Molecular Dynamics

[1] Computer simulation of structure and microphase separation in model A-B-A triblock copolymers, M. Banaszak, S. Woloszczuk, T. Pakula and S. Jurga,

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[2] Lamellar ordering in computer-simulated block copolymer melts by a variety of thermal treatments, M. Banaszak, S. Woloszczuk, S. Jurga and T. Pakula, J. Chem. Phys., 119, 11451-11457 (2003)

[3] Computer Simulation of Microphase Separation in Ionic Copolymers M. Banaszak and J.H.R. Clarke, <u>Phys. Rev. E</u>, 60, 5753-5757(1999) Monte Carlo

lattice model

Molecular Dynamics

off-lattice model

triblock and diblock copolymers

very short-range potential

more coarse-grained

ionic diblock copolymers

long-range electrostatic potential

less coarse-grained



Spheres of B in A



Layers

Cylinders of A in B

Spheres of A in B



Block copolymers are important selfassembling materials for the following reasons:

- Precise (and continuous) control over lengthscales - from 5 to 50 nm
- Control over morphology- L, C, G and S for diblocks and over 30 for triblocks
- Possibility of selecting the polymer for each block
- Quantitative prediction of equilibrium structures -SCMF

Applications of Block Copolymers

"Old" - retain important features of their constituent homopolymers, do not take advantage of any particular nanostructure

"New" - depend on long-range organization and orientation of the nanostructure

Challenges

Synthesis and preparation of materials
New nanostructures (theory and simulation)

Fory-ligging Theory

$$f_{m} = \frac{\phi_{A}}{N_{A}} \ln \varphi_{A} + \frac{1}{N_{A}} \log \varphi_{A} + \frac{1}{N_{A}} \log \varphi_{A}$$
$$\varphi_{A} + \varphi_{B} = 1$$
$$- \varepsilon_{AA}, -\varepsilon_{AB}, -\varepsilon_{BB}$$
$$\chi = \frac{z}{2kT} [\varepsilon_{AA} + \varepsilon_{AB}]$$



Reduced Temperature, T*/N

■ *E* - interaction energy between A and B $\blacksquare T^* = kT/\epsilon$ $\mathbf{\nabla} \chi = (z - 2)/T^*$ Leibler's RPA theory (mean field) < Flory interaction χ parameter < N - copolymer chain length (number of monomeric units) $< N \chi = 10.5$ - ODT for symmetric diblocks $< T^*/N$ - the copolymer reduced temperature

Triblock microarchitectures



10-10-10 7-16-7 3-24-3

30 x 30 x 30 60 x 30 x 30 60 x 60 x 60

Simulation box, 60x30x30



Lamellar nanostructures



Bicontinuous nanostructure for the 10-10-10 microarchitecture, T*/N=0.04



7-16-7 Microarchitecture, T*/N=0.04





7-16-7 Microarchitecture, T*/N=0.04



3-24-3 Microarchitecture, T*/N=0.04





Phase diagram of the sympetric tribloc copolymer melt







Lamellar nanostructures



A parameter - low-temperature lamellar ordering



Bridges and Loops















Diblock melts

8-8 microarchtekture





Lamellar reorientation



bric Block Copolymer

 $\Phi_{WCA}(r_{ij}) = 4\epsilon((\sigma/r_{ij})^{12} - (\sigma/r_{ij})^6) + \epsilon r_{ij} < 2^{1/6}\sigma$











Conclusion

- MD simulation for triblock and diblock copolymers
- Microphase separation as a function of pressure
- Experimental search for low-temperature ordering effects in block copolymer melts
- New efficient algorithms for copolymer simulations